

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of	)	
Charles W. Schietinger et al.	)	Group Art Unit: 2877
Application No.: 10/672,558	)	Examiner: Roy M. Punnoose
Filed: September 26, 2003	)	Confirmation No.: 3875
For: OPTICAL TECHNIQUES FOR	)	<b>HAND DELIVERY</b>
MEASURING LAYER THICKNESSES	)	
AND OTHER SURFACE	)	
CHARACTERISTICS OF OBJECTS	)	
SUCH AS SEMICONDUCTOR	)	
WAFERS	)	

COMMUNICATION REGARDING FOREIGN REFERENCES

Examiner Punnoose, Art Unit 2877  
Office No. 6B49  
Jefferson Building  
500 Dulany Street  
Alexandria, VA 22313

Dear Examiner Punnoose:


Pursuant to your request, enclosed please find three 1449 Forms and copies of the corresponding foreign references for your files.

If you have any questions please do not hesitate to contact me.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

Date: January 6, 2005

By:   
Eric K. Proul  
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FORM PT01449  
(REV. 8-83)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
LUXT.118US1SERIAL NO.  
09/577,795

## INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

APPLICANT  
Charles W. Schietinger et al.FILED  
May 24, 2000GROUP  
2878

## U. S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
	A12	5 8 3 5 2 2 5	11/10/1998	Thakur			
	A13	5 8 3 8 4 4 7	11/17/1998	Hiyama et al.			
	A14	5 8 3 8 4 4 8	11/17/1998	Aiyer et al.			
	A15	5 8 5 1 1 3 5	12/22/1998	Sandhu et al.			
	A16	5 8 7 2 6 3 3	2/16/1999	Holzapfel et al.			
	A17	5 8 9 9 7 9 2	5/04/1999	Yagi			
	A18	5 4 1 6 5 9 4	5/16/1995	Gross et al.			
	A19	5 4 9 9 7 3 3	3/19/1996	Litvak			
	A20	5 5 5 5 4 7 4	9/10/1996	Ledger			

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANS.? (YES/NO)
✓	B6	0 4 1 2 7 2 8 A2	2/13/1991	European Patent Application			
✓	B7	0 7 3 5 5 6 5 A1	10/02/1996	European Patent Application			
✓	B8	0 7 3 8 5 6 1 A1	10/23/1996	European Patent Application			
✓	B9	0 8 2 4 9 9 5 A1	2/25/1998	European Patent Application			
✓	B10	wo 9 3 2 5 8 9 3	12/23/1993	PCT			
✓	B11	wo 9 5 1 8 3 5 3	7/06/1995	PCT			
✓	B12	wo 9 7 2 5 6 6 0	7/17/1997	PCT			

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent pages, Etc.)

C4	Schietinger, C., "Wafer Emissivity in RTP," F. Roozeboom (ed.), <u>Advances in Rapid Thermal and Integrated Processing</u> , pps. 125-141, (1996) Kluwer Academic Publishers, Printed in the Netherlands
C5	Fang, S.J. et al., "Control of Dielectric Chemical Mechanical Polishing (CMP) Using an Interferometry Based Endpoint Sensor," <u>Proceedings of the IEEE 1998 International Inconnect Technology Conference</u> , Hyatt Regency Hotel, San Francisco, CA, pps. 98-76 to 98-78 (June 1-3, 1998)
C6	Bibby, T. et al., "Endpoint Detection for CMP," <u>Journal of Electronic Materials</u> , Vol. 27, No. 10, pps. 1073 - 1081 (1998)
C7	Berman, M. et al., "Review of In Situ & In-line Detection for CMP Applications," <u>Semiconductor Fabtech - 8th Edition</u> , Article contains eight pages.

EXAMINER

DATE CONSIDERED

\* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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## APPLICANT

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## U. S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER								DATE	NAME	CLASS	SUB CLASS	FILING DATE
	A1	4	2	9	3	2	2	4		10/06/1981	Gaston et al.			
	A2	5	1	6	6	0	8	0		11/24/1992	Schietinger et al.			
	A3	Re	3	4	4	2	5			11/02/1993	Schultz			
	A4	5	3	0	8	4	4	7		5/03/1994	Lewis et al.			
	A5	5	4	3	3	6	5	1		7/18/1995	Lustig et al.			
	A6	5	4	8	6	7	0	1		1/23/1996	Norton et al.			
	A7	5	5	6	4	8	3	0		10/15/1996	Böbel et al.			
	A8	5	5	6	8	2	5	2		10/22/1996	Kusuda et al.			
	A9	5	6	0	9	5	1	1		3/11/1997	Moriyama et al.			
	A10	5	7	2	4	1	4	4		3/03/1998	Muller et al.			
	A11	5	7	6	9	5	4	0		6/23/1998	Schietinger et al.			

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		DOCUMENT NUMBER								DATE	COUNTRY	CLASS	SUB CLASS	TRANS.? (YES/NO)
✓	B1	6	2	1	9	0	7	2	8	8/20/1987	EPO - Patent Abstracts of Japan			
✓	B2	6	2	1	9	0	7	2	8A	8/20/1987	Derwent Publ.-Japanese Abstract			
✓	B3	6	2	1	9	0	7	2	8	8/20/1987	Japan			Yes
✓	B4	0	8	3	3	9	9	8	2	12/24/1996	Japanese Patent Office			Abstract
✓	B5	0	3	5	2	7	4	0	B1	5/01/1996	European Patent Specification			

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent pages, Etc.)

	C1	Williams, C.S. et al., "Emissivity, Reflectance, Absorptance, and Transmittance," <u>OPTICS: A Short Course for Engineers &amp; Scientists</u> , pps. 31-35, (1984)
	C2	Litvak, H.E. et al., "Implementing Real-Time Endpoint Control in CMP," <u>Semiconductor International</u> , Vol. 19, No. 8, pps. 259-264 (July 1996)
	C3	Schietinger C., "Wafer Temperature Measurement in RTP," F. Roozeboom (ed.), <u>Advances in Rapid Thermal and Integrated Processing</u> , pps. 103-123, (1996) Kluwer Academic Publishers. Printed in the Netherlands

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